

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1.-12. (Canceled)

13. (Currently Amended) A device formed by a first body and a second body welded together through a mechanical and electrical connection structure, comprising:

an electrically conductive region welded between said first body and said second body; and

a spacing region arranged near said electrically conductive region and surrounding an active region of said electromechanical system.

14. (Original) The device according to claim 13, wherein said electrically conductive region is of a low-melting eutectic material.

15. (Original) The device according to claim 14, wherein said low-melting eutectic material is formed by alternating layers of gold and tin.

16. (Original) The device according to claim 13, wherein said spacing region is of dielectric material.

17. (Original) The device according to claim 16, wherein said dielectric material is chosen from among a spun polymer, such as SU8, polyimide, a composite material formed by laminated polymer layers, such as a photosensitive stick foil, and oxynitrides.

18. (Original) The device according to claim 13, wherein said spacing region forms a delimiting cavity surrounding said electrically conductive region.

19. (Currently Amended) The device according to claim 13—, further comprising a metal region which extends on top of said second body and beneath said electrically conductive region.

20. (Original) The device according to claim 19, wherein said welding region and said metal region are of a material chosen from among titanium, gold and nickel.

21.-26. (Canceled)

27. (Currently Amended) A device comprising:
a first body of semiconductor material;
a first metal region, formed on a first surface of the first body;
a second body of semiconductor material spaced apart from the first body;
a spacer separating the first and second body and in contact with the first surface of the first body and a first surface of the second body, the spacer defining an enclosed space between the first and second bodies;
a second metal region, formed on a first surface of the second body; and
a connection structure bonded to the first and second metal regions, forming thereby an electrical connection between the first and second metal regions.

28. (Original) The device of claim 27 wherein the connection structure is a low-melting eutetic material welded to the first and second metal regions.

29. (Currently Amended) The device of claim 27 wherein ~~the spacer defines an enclosed space between the first and second bodies,~~ the first and second metal regions and the connection structure are formed within the enclosed space defined by the spacer.

30. (Currently Amended) The device of claim 27 wherein ~~the spacer defines an enclosed space between the first and second bodies, within which is formed a micromechanical structure~~ is formed within the enclosed space defined by the spacer.

31. (Original) The device of claim 27 wherein the first body of semiconductor material is formed of quartz.

32. (Original) The device of claim 31, further comprising a mirror formed on a second surface of the first body.

33. (Original) The device of claim 31, further comprising a diffractive lens formed on the second surface of the first body.

34. (New) The device of claim 13 wherein the device comprises an electromechanical, fluid and optical system.

35. (New) The device of claim 13, wherein the active region comprises an electromechanical structure.

36. (New) The device of claim 13, wherein the active region comprises an optical structure.

37. (New) The device of claim 36, further comprising a mirror formed on a surface of the first body opposite the optical structure.

38. (New) The device of claim 36, further comprising:
a third body welded to the first body adjacent to the second body; and
a spacing region formed between the first and third bodies and surrounding an additional active region.

39. (New) The device of claim 38, further comprising first and second mirrors formed on opposite faces of the first body.

40. (New) The device of claim 13 wherein the first and second bodies are wafers of semiconductor material.

41. (New) The device of claim 13 wherein the spacing region completely surrounds the active region.